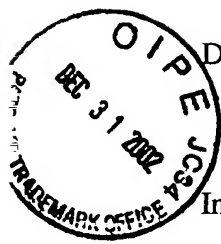


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Docket No.: 004066 USA D01/Consilium/Consilium

PATENT/OFFICIAL

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of

John F. ARACKAPARAMBIL et al.

Serial No. 10/084,092

Filed: February 28, 2002

For: COMPUTER INTEGRATED MANUFACTURING TECHNIQUES

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Group Art Unit: 2121

Examiner:

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SUPPLEMENTAL INFORMATION DISCLOSURE STATEMENT

Honorable Commissioner for Patents
Washington, D.C. 20231

Sir:

In accordance with the provisions of 37 C.F.R. 1.56, 1.97 and 1.98, the attention of the Patent and Trademark Office is hereby directed to the documents listed on the attached form PTO-1449. It is respectfully requested that the documents be expressly considered during the prosecution of this application, and that the documents be made of record therein and appear among the "References Cited" on any patent to issue therefrom. Copies of the references listed on pages 1 and 2 of Form PTO-1449 are submitted herewith.

This Information Disclosure Statement is being filed within three months of the U.S. filing date OR before the mailing date of a first Office Action on the merits. No certification or fee is required.

This submission does not constitute a representation that a search has been made or that no better art exists and does not constitute an admission or representation that any of the listed documents is material or constitutes prior art. If it should be determined that any of the listed documents does not constitute prior art under the United States law, Applicants reserve the right

Serial No. 10/084,092

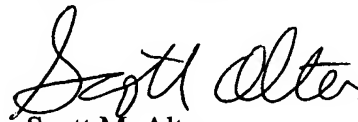
to present to the Office the relevant facts and law regarding the appropriate status of such document.

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No certification or fee is believed to be required. However, the Commissioner is hereby authorized to charge any additional fees should any be required for this submission, or credit any overpayment to deposit account no. 08-0219.

Respectfully submitted,

HALE AND DORR LLP



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Date: 12/31/02

**INFORMATION DISCLOSURE
CITATION IN AN
APPLICATION**

(PTO-1449)



ATTY. DOCKET NO.
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D01/Consilium/Consilium

SERIAL NO.
10/084,092

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APPLICANT
John F. ARACKAPARAMBIL et al.

FILING DATE
February 28, 2002

GROUP
2121

U.S. PATENT DOCUMENTS

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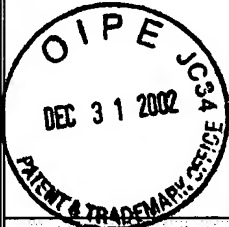
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EXAMINER'S INITIALS	PUBLICATION / PATENT NO.	DATE	COUNTRY	CLASS	SUBCLASS	Translation	
						Yes	No
	WO 95/34866 ✓	12/21/95	WO			X	
	WO 98/45090 ✓	10/15/98	WO			X	
	EP 0 881 040 A2 ✓	12/02/98	Europe			X	
	WO 99/25520 ✓	05/27/99	WO			X	
	WO 00/54325 ✓	09/14/00	WO			X	
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EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; draw line through citation if not in conformance and not considered. Include copy of this form with next communication to Applicant.

INFORMATION DISCLOSURE CITATION IN AN APPLICATION  (PTO-1449)				ATTY. DOCKET NO. 004066 USA D01/Consilium/Consilium		SERIAL NO. 10/084,092	
				APPLICANT John F. ARACKAPARAMBIL et al.			
				FILING DATE February 28, 2002		GROUP 2121	
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